A Fast Area Efficient Sense-Amp (Case Study)

G. Fredeman et al., "A 14 nm 1.1 Mb Embedded DRAM Macro With 1 ns Access," in IEEE Journal of Solid-State Circuits, vol. 51, no. 1, pp. 230-239, Jan. 2016. doi: 10.1109/JSSC.2015.2456873

Problems with Micro Sense Amp

- By default the Sense Amp reads a 0
- □ Access transistor has to pull the LBL HIGH to read 1
 - □ Asymptotic charge up to High since Vgs keeps reducing
 - Very slow by nature
 - □ Need to minimize the WLs per BL(33) for performance reasons
- □ Cannot pre-charge LBL to High
 - □Floating Body Effect affects retention
- □ NMOS (Access Device) is very fast when pulling down to zero
 - □ Can we make a Sense Amp that reads a one by default?
 - □ This will allow more WLs per BL

LBL Pre-charge vs Pre-discharge



Introduction of eDRAM

Slide 3

Basic Structure





































19-Apr-18

















Area Savings and Comparison with 3T uSA



Introduction of eDRAM













One Data Line Organization



- Single bit can be read out/ written into by selecting one of 128 rows and one of 8 columns
- The components are sized and arranged to make the layout nice and rectangular
- Repeat this structure as many as there are Data-lines

14nm FinFET Advantage



14nm Access Device is 2.5X stronger than the 22nm planar device due to

- 50% more effective width
- 42% shorter channel length
- Lower target Vth

Lower VT variation due to undoped channel

Lower Vth Variation Effect on Retention



- Write a 1 into all the cells
- Read the cells after a pause time
- Ideally (with no local variations) there should be an step jump in the #fail
 - With variations, steeper the slope lesser the variations

Conclusion

- Pulling more DRAM cache (L2,L3) inside the processor improves overall performance
- eDRAM design using logic process is a challenge
- Case study is done, covering many of the eDRAM design aspects
- Sense amp has to read a 1 by default to provide performance improvement

Achieved in the Gated Feedback Sense Amp

References

- Matick, R. et al., "Logic-based eDRAM: Origins and Rationale for Use," IBM J. Research Dev., vol. 49, no. 1, pp. 145-165, Jan. 2005.
- Barth, J. et al., "A 500MHz Random Cycle 1.5ns-Latency, SOI Embedded DRAM Macro Featuring a 3T Micro Sense Amplifier," ISSCC Dig. Tech. Papers, pp. 486-487, Feb. 2007.
- Barth, J. et al., "A 500 MHz Random Cycle, 1.5 ns Latency, SOI Embedded DRAM Macro Featuring a Three-Transistor Micro Sense Amplifier," IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 43, NO. 1, JANUARY 2008.
- Barth, J. et al., "A 45nm SOI Embedded DRAM Macro for POWER7TM 32MB On-Chip L3 Cache," ISSCC Dig. Tech. Papers, pp. 342-3, Feb. 2010.
- Barth, J. et al., "A 45 nm SOI Embedded DRAM Macro for the POWER™ Processor 32 MByte On-Chip L3 Cache," IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 46, NO. 1, JANUARY 2011.
- S. Iyer et al., "Embedded DRAM: Technology Platform for BlueGene/L Chip," IBM J. Res. & Dev., Vol. 49, No. 2/3, MARCH/ MAY 2005, pp.333-50.
- Barth, J. et al., "A 300MHz Multi-Banked eDRAM Macro Featuring GND Sense, Bit-line Twisting and Direct Reference Cell Write," ISSCC Dig. Tech. Papers, pp. 156-157, Feb. 2002.
- Barth, J. et. al., "A 500-MHz Multi-Banked Compilable DRAM Macro With Direct Write and Programmable Pipelining," IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 40, NO. 1, JANUARY 2005.
- Butt, N., et al., "A 0.039um2 High Performance eDRAM Cell based on 32nm High-K/Metal SOI Technology," IEDM pp. 27.5.1-2, Dec 2010.
- Bright, A. et al., "Creating the BlueGene/L Supercomputer from Low-Power SoC ASICs," ISSCC Dig. Tech. Papers, pp. 188-189, Feb. 2005.
- Blagojevic, M. et al., "SOI Capacitor-Less 1-Transistor DRAM Sensing Scheme with Automatic Reference Generation," Symposium on VLSI Circuits Dig. Tech. Papers, pp. 182-183, Jun. 2004.

References

Karp, J. et al., "A 4096-bit Dynamic MOS RAM" ISSCC Dig. Tech. Papers, pp. 10-11, Feb. 1972.

- Kirihata, T. et al., "An 800-MHz Embedded DRAM with a Concurrent Refresh Mode," IEEE Journal of Solid State Circuits, pp. 1377-1387, Vol. 40, Jun. 2003.
- Luk, W. et al., "2T1D Memory Cell with Voltage Gain," Symposium on VLSI Circuits Dig. Tech. Papers, pp. 184-187, Jun. 2004.
- Luk, W. et al., "A 3-Transistor DRAM Cell with Gated Diode for Enhanced Speed and Retention Time," Symposium on VLSI Circuits Dig. Tech. Papers, pp. 228-229, Jun. 2006.

NEC eDRAM Cell Structure (MIM Capacitor): http://www.necel.com/process/en/edramstructure.html

- Ohsawa, T. et al., "Memory Design using One-Transistor Gain Cell on SOI," ISSCC Dig. Tech. Papers, pp. 152-153, Feb. 2002.
- Pilo, H. et al., "A 5.6ns Random Cycle 144Mb DRAM with 1.4Gb/s/pin and DDR3-SRAM Interface," ISSCC Dig. Tech. Papers, pp. 308-309, Feb. 2003.
- Taito, Y. et al., "A High Density Memory for SoC with a 143MHz SRAM Interface Using Sense-Synchronized-Read/Write," ISSCC Dig. Tech. Papers, pp. 306-307, Feb. 2003.
- Wang, G. et al., A 0.127 mm2 High Performance 65nm SOI Based embedded DRAM for on-Processor Applications," International Electron Devices Meeting, Dec. 2006.

G. Fredeman et al., "A 14 nm 1.1 Mb Embedded DRAM Macro With 1 ns Access," in IEEE Journal of Solid-State Circuits, vol. 51, no. 1, pp. 230-239, Jan. 2016. doi: 10.1109/JSSC.2015.2456873